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STIC Database Tracking Number: 183671

**TO: Paul Prebilic
Location: RND 6c03
Art Unit: 3993
Thursday, March 30, 2006**

Case Serial Number: 10/066769

**From: Terry Solomon
Location: EIC 3700
RND 8b31
Phone: 272-4240**

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Search Notes

No current or past litigation found involving US pat. 6301801.

Sources:

Lexis/Nexis
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Patent Search - Number: 6,301,801

No cases found.

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552572 (09) 6301801 October 16, 2001

UNITED STATES PATENT AND TRADEMARK OFFICE GRANTED PATENT

6301801

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October 16, 2001

Vacuum processing apparatus and operating method therefor

REISSUE: February 6, 2002 - Reissue Application filed Ex. Gp.: 2162; Re. S.N. 10/066,769 (O.G. October 15, 2002)

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** SS 1: Results 1
PRT SS 1 MAX 1 LEGALALL

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Patent Number :

US6301801 B1 20011016 [US6301801]

Title :

(B1) Vacuum processing apparatus and operating method therefor

Inventor(s) :

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(JP); ITOU ATSUSHI (JP)

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Cont. of US443039 19950517 [1995US-0443039]
Divsn of US302443 19940909 [1994US-0302443]
Cont. of US096256 19930726 [1993US-0096256]
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Continuation of: US5784799
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JP22532190 19900829 [1990JP-0225321]
US6106298 19980416 [1998US-0061062]
US9625693 19930726 [1993US-0096256]
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US59387096 19960130 [1996US-0593870]
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US88273197 19970626 [1997US-0882731]

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IPC Advanced All :

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H01L-021/677 [2006-01 A - I R M EP]

IPC Core All :

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H01L-021/67 [2006 C - I R M EP]

EPO ECLA Class :

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H01L-021/00S2Z
H01L-021/00S8B
H01L-021/677

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US Patent Class :

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JP60-246635; JP62-44571; JP62-50463; JP62-89881; JP62-207866;
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JP1-251734; JP1298180; JP1-310553; JP2-61064; JP265252; JP294647;
JP2-106037; JP430549; WO8707309
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4, pp. 38-43, Apr. 10, 1987 (w/translation).

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Abstract :

This invention relates to a vacuum processing apparatus having vacuum
processing chambers the insides of which must be dry cleaned, and to a
method of operating such an apparatus. When the vacuum processing
chambers are dry-cleaned, dummy substrates are transferred into the
vacuum processing chamber by substrates conveyor means from dummy
substrate storage means which is disposed in the air atmosphere together
with storage means for storing substrates to be processed, and the
inside of the vacuum processing chamber is dry-cleaned by generating a
plasma. The dummy substrate is returned to the dummy substrate storage
means after dry cleaning is completed. Accordingly, any specific
mechanism for only the cleaning purpose is not necessary and the
construction of the apparatus can be made simple. Furthermore, the dummy
substrates used for dry cleaning and the substrates to be processed do
not coexist, contamination of the substrates to be processed due to dust
and remaining gas can be prevented and the production yield can be
high.

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1 / 1 CRXX - ©CLAIMS/RRX

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Patent Assignee :

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Tsunehiko JP

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